

Rigorous eBeam and SEM Simulation

Rigorous Mask 3D Simulation (EUV and ArF)











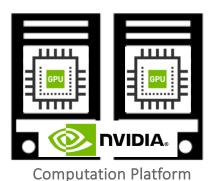
Wafer

Verification











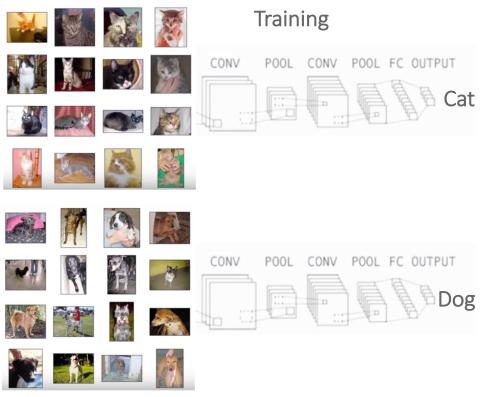
Deep Learning Engine(s)

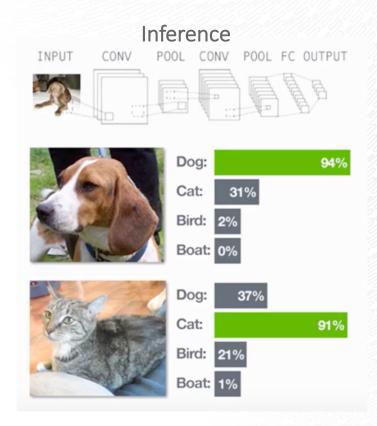


Pre-trained Deep Learning
Neural Networks



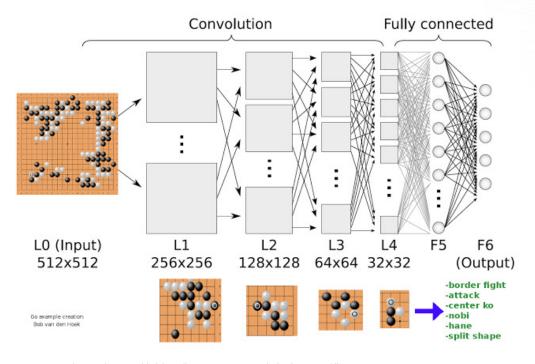
Deep Learning (DL) Doesn't "Reason" – It Pattern Matches







But With Tireless Learning From Pattern-Matching, Deep Learning (DL) Can "Out-think" Humans



Source: Bob van den Hoek's blog, "Deep Learning: Sky's the Limit?"

100M games in 4~6 weeks

10K games in life time







"Enough Data" Needed to Learn Similar Situations



But some situations are too dangerous or rare for "real life" training



Simulation: Test, Validate Billions of Miles Safely

- Deep Learning (DL) training focuses on corner cases
 - Millions of similar "normal" driving miles don't add to the learning
- Simulation allows combinations of effects to be automatically generated
 - Traffic, weather, accidents...
- Indispensable for debugging
 - Controlled environment
 - Easy fault insertion
 - Learning without machine time

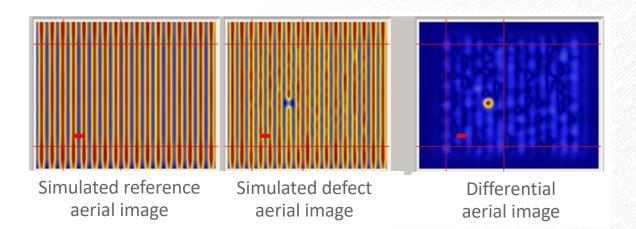




Simulation Offers the Same Advantages for Deep Learning (DL) in Semiconductor Manufacturing

Simulated mask inspection images



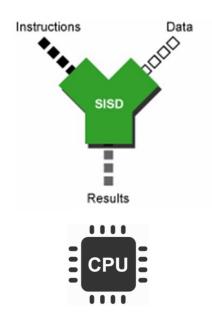


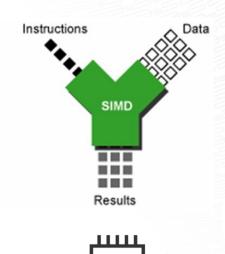
Defects Are a Very Small Percentage of all masks and wafers, But for Deep Learning Training, We Need A LOT of Them

Source: L. Pang, et. al, "Computational inspection applied to a mask inspection system with advanced aerial imaging capability", SPIE Advanced Lithography, 2010



GPU Excels at Simulation and Training for Deep Learning





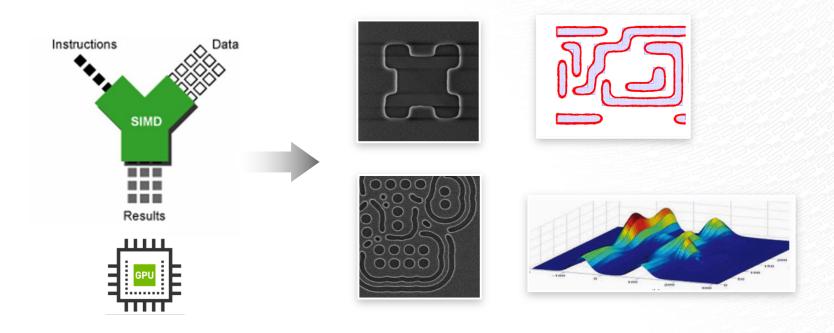








GPU Also Excels at Mask and Wafer Simulation



GPU (SIMD) is perfect for pixel data, which is shape-independent



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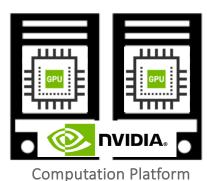


Verification











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Platform Application: D2S Project at CDLe

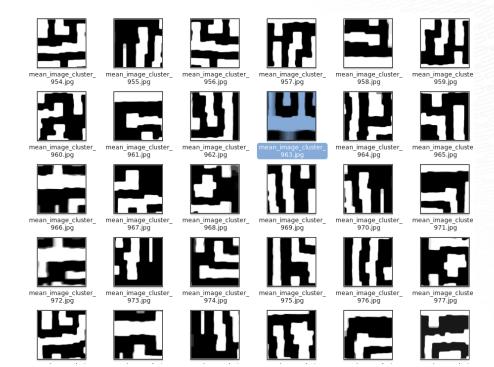
CENTER FOR DEEP LEARNING IN ELECTRONICS MANUFACTURING

A PARTNERSHIP OF NUFLARE MYCRONIC DES



DL Mask Pattern Classifier Trained with Simulated Mask Pattern and Autoencoder

Different Groups Classified by Deep Learning



DL Mask Pattern Classifier Trained with Simulated Mask Pattern and Autoencoder





Sum images of Group 963

of Group 963



ras_design_lr_61070.



















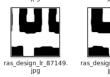


























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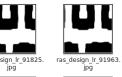


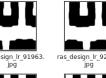
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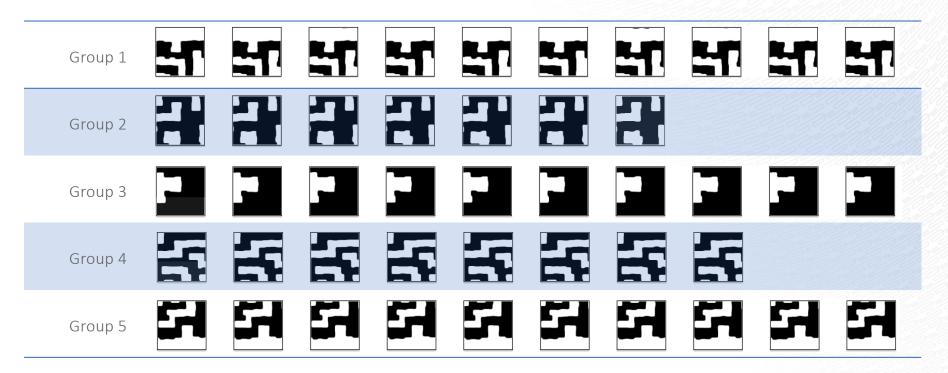








DL Mask Pattern Classifier Trained with Simulated Mask Pattern and Autoencoder









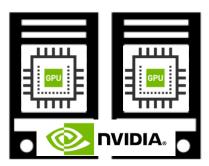












Computational Design Platform (CDP)







GPU-Accelerated Computational Design Platform

- For Deep Learning Acceleration at CDLe
 - 500 TFLOPS SP computing power with NVIDIA V100
 - Reliable, Redundant, Recoverable for 24/7 Clean Room Operations

 Integrated Solution for GPU-Accelerated Deep Learning





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Wafer Simulation



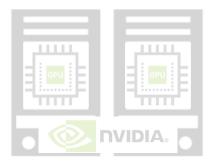


Verification









Computational Design Platform (CDP)



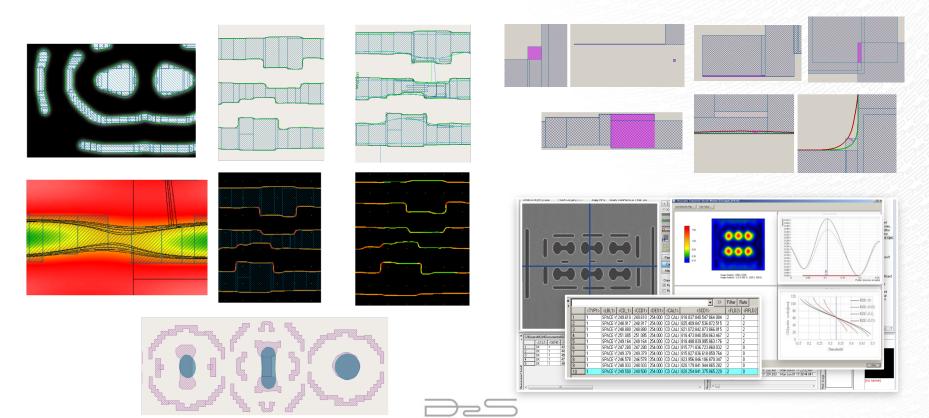
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D2S TrueMask®: GPU-Accelerated Curvilinear Mask/Litho Simulators, Geometry Engine, Verification for DL Training



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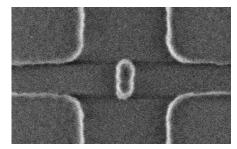




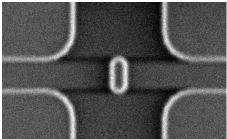


GPU-Accelerated Rigorous eBeam/SEM Simulators and EUV Mask 3D Simulators from Partners for DL Training



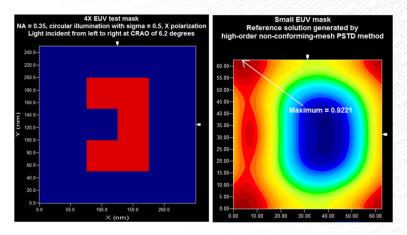


Actual SEM



Simulated SEM





Fast Rigorous EUV Mask 3D Simulation



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Rigorous Mask 3D imulation (EUV and ArF



Wafer Simulation























Verification





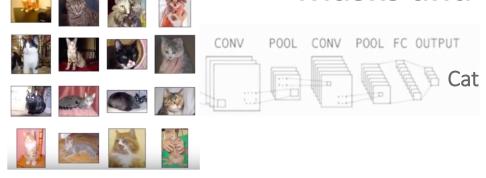


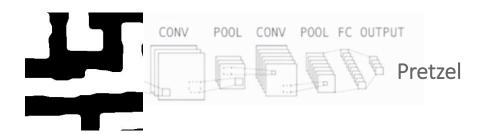


Platform (CDP)



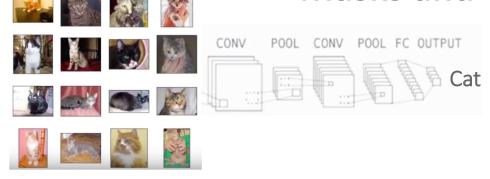
Pre-Trained Deep Learning Neural Network Models for Masks and Wafers







Pre-Trained Deep Learning Neural Network Models for Masks and Wafers



Pre-trained DL Neural Network Model for Mask and Wafer The network
training required
to identify a cat is
very different
from the network
training required
to identify a
wafer defect

→ Hotspot/Defect Classification



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Wafer Simulation











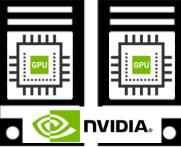




Geometry Libraries







Computational Design Platform (CDP)









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